

wherein removing the sacrificial material comprises suspending the second structural material as a second structure coupled to the first structure.

8. (Twice Amended) A method comprising:

over an area of a surface of a substrate, lithographically patterning a plurality of first structures, the plurality of first structures having a first dimension about the surface of the substrate and a second different dimension;

following forming the first structures, conformally introducing a sacrificial material layer over the area of the substrate;

patterning the sacrificial material;

forming second structures over the sacrificial material;

removing the sacrificial material; and

wherein removing the sacrificial material comprises suspending the second structure by the first structure.